

ĐẠI HỌC QUỐC GIA TP. HCM
TRƯỜNG ĐẠI HỌC BÁCH KHOA



MÔN HỌC: THIẾT KẾ VI MẠCH

BÁO CÁO LAB 1
MOS TRANSISTOR CHARACTERIZATION

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TP. HỒ CHÍ MINH, NĂM 2021

LABORATORY 1

MOS TRANSISTOR CHARACTERIZATION

OBJECTIVES

No.	Objective	Requirement
1	I-V characteristics of MOS transistors.	<ul style="list-style-type: none"> Simulating curves I_D vs V_{GS}, and I_D vs V_{DS} of <i>NMOS_VTL</i> and <i>PMOS_VTL</i> transistors.
2	The effects on I-V characteristics when varying: <ul style="list-style-type: none"> ➤ V_{GS}. ➤ Device's size. 	<ul style="list-style-type: none"> Simulating curves I_D vs V_{GS}, and I_D vs V_{DS} of <i>NMOS_VTL</i> transistor, then observing the curves drawn.
3	Create layouts for MOS transistors.	<ul style="list-style-type: none"> Create layouts for a <i>120n/60n NMOS_VTL</i> and a <i>50n/50n PMOS_VTL</i>. Show DRC confirmation and corresponding schematic with proof of LVS.

PREPARATION FOR LAB 1

- Students **must finish** lab 0 at home.



EXPERIMENT 1

Objective: Known MOS transistor operations and I-V curves.

Requirements: Procedure I_D vs V_{GS} , and I_D vs V_D plots of NMOS_VTL and PMOS_VTL in FreePDK45.

Instructions: Assemble the circuit as shown in **Figure 1**, setting parameters for power supplies (using **vdc** source).

Check: Your report must show these results for both NMOS_VTL transistors.

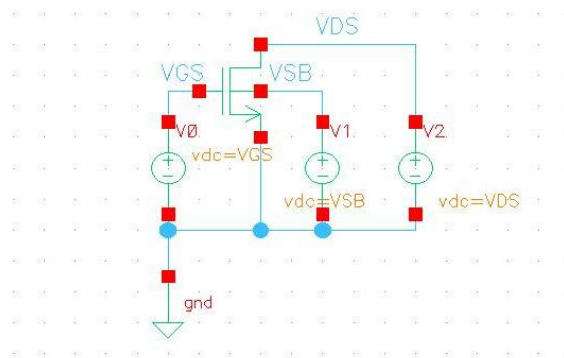
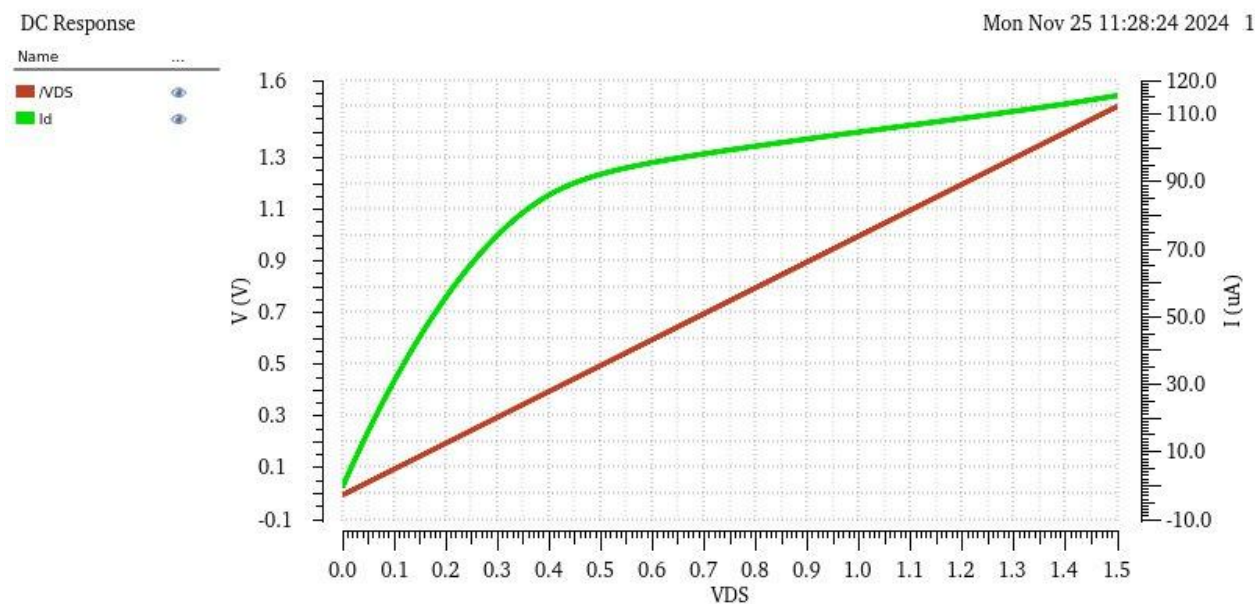


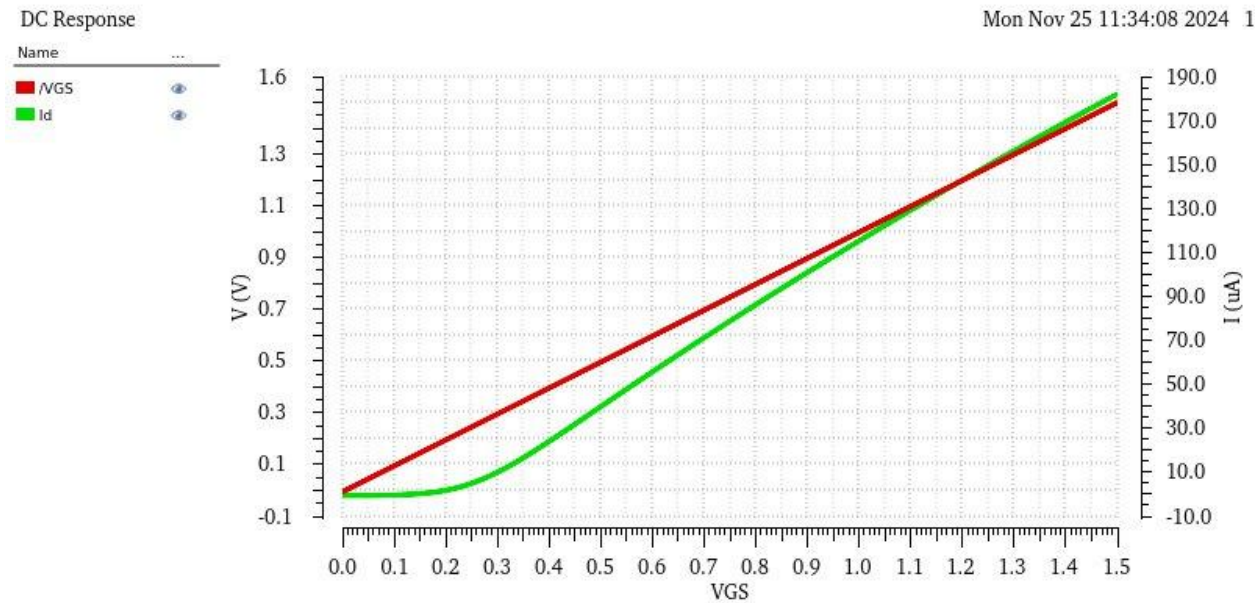
Figure 1 Test setup for the NMOS_VTL transistor.

- Simulate curves I_D vs V_{DS} @ $V_{GS} = 1V$, and sweeping variable $V_{DS} = [0, 1.5]V$ step 10mV.



LABORATORY 1 – MOS TRANSISTOR CHARACTERIZATION

- Simulate curves I_D vs V_{GS} @ $V_{ds} = 1.5V$, and sweeping variable $V_{gs} = [0,1.5]V$ step 10mV.



Check: Your report must show these results for both PMOS_VTL transistors.

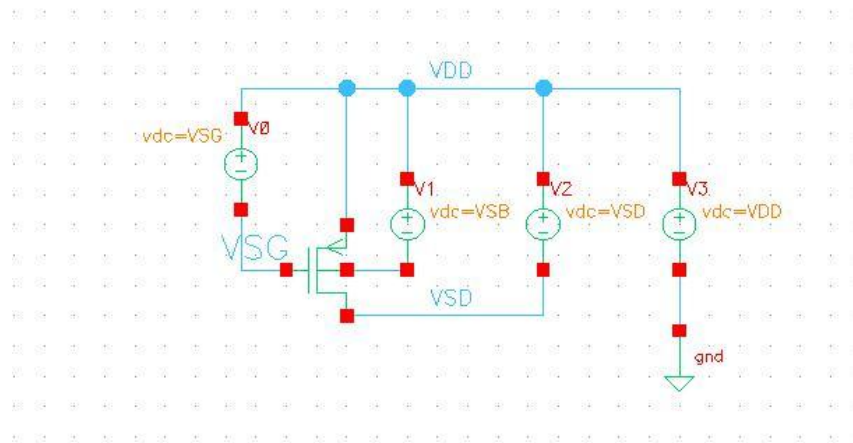
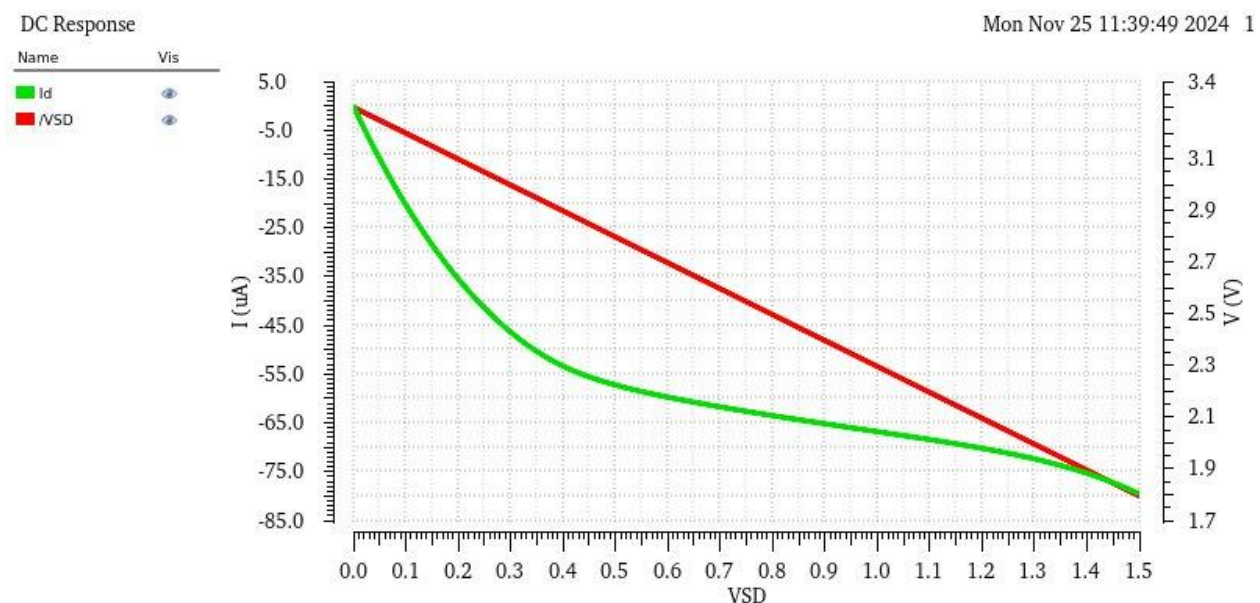


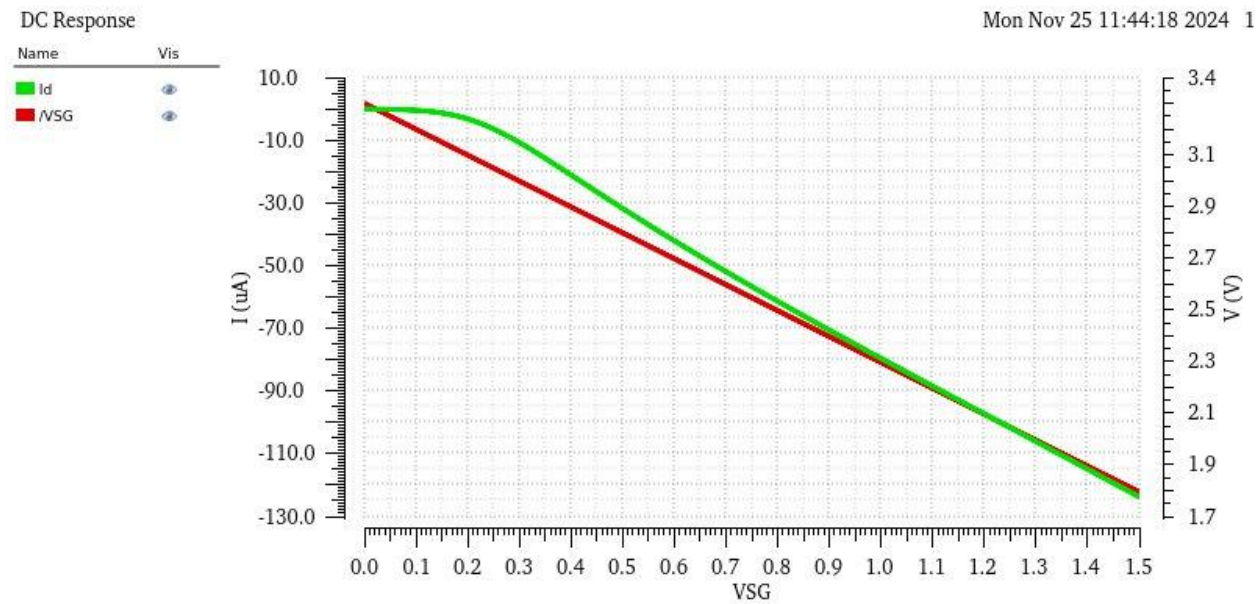
Figure 2 Test setup for PMOS_VTL transistor.

- Simulate curves I_D vs V_{DS} @ $V_{GS} = 1V$, and sweeping variable $V_{DS} = [0,1.5]V$ step 10mV.



LABORATORY 1 – MOS TRANSISTOR CHARACTERIZATION

➤ Simulate curves I_D vs V_{GS} @ $V_{ds} = 1.5V$, and sweeping variable $V_{gs} = [0, 1.5]V$ step 10mV.



EXPERIMENT 2

Objective: The effects on IV characteristics when varying V_{GS} , and the device's size. **Requirements:** Simulate curves I_D vs V_{DS} and I_D vs V_{GS} when varying V_{GS} , and device's size. **Instructions:**

➤ Replace the default size of the NMOS transistor with variables W, and L, respectively. It means your testbench has five parameters W, L, V_{GS} , V_{DS} , and V_{SB} shown in the figure below.

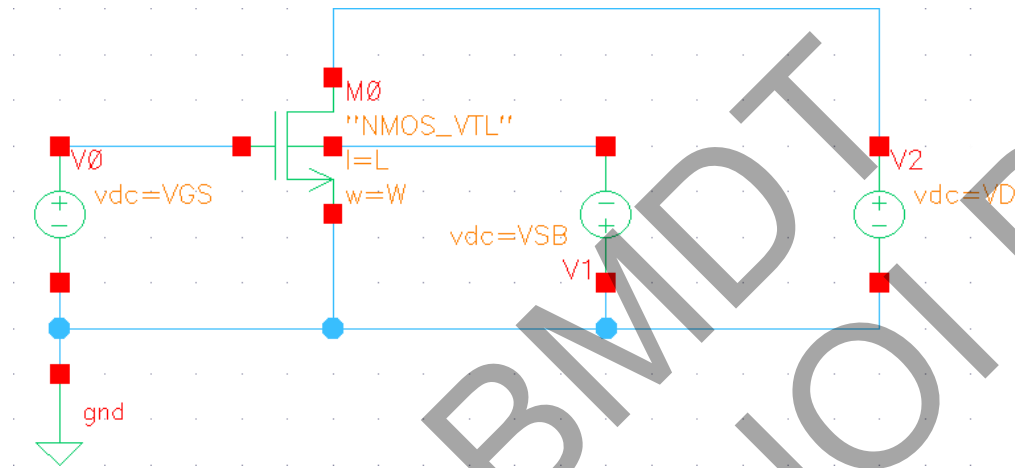


Figure 3 Testbench for experiment 2.

➤ In ADE-L, students open Parametric Analysis to sweep multiple variables:

Tool > Parametric Analysis > Run mode > Sweeps & Ranges

➤ **Parametric analysis** is used when two or more independent variables are present in a single function. Students can have the standard X-Y plot of I_D versus V_{DS} with a constant V_{GS} . But students need to plot the same X-Y plot multiple times for each of the discrete V_{GS} values. Students can refer to the settings and results in the figures below:

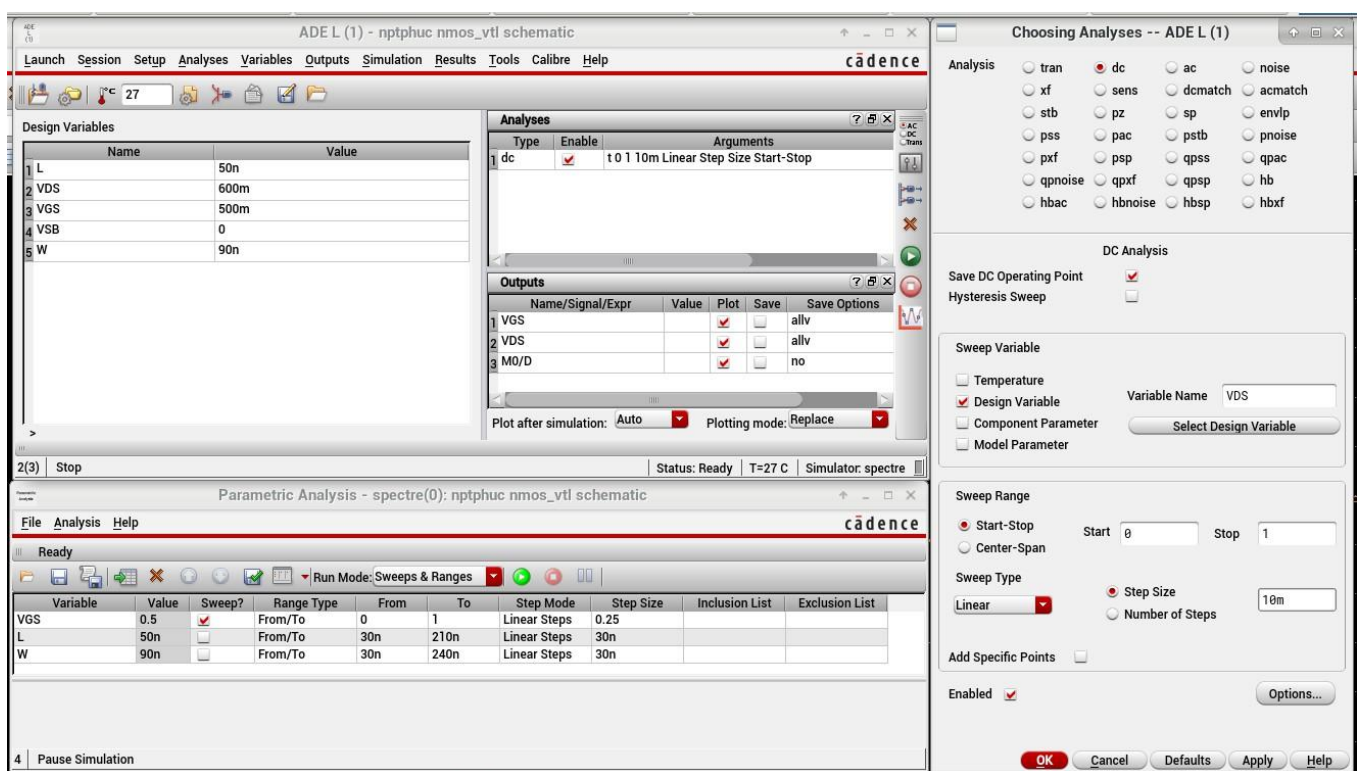


Figure 4 Setting parameters for characterizing I_D vs V_{DS} @ $V_{GS} = \{0, 0.25, 0.5, 0.75, 1.0\} V$

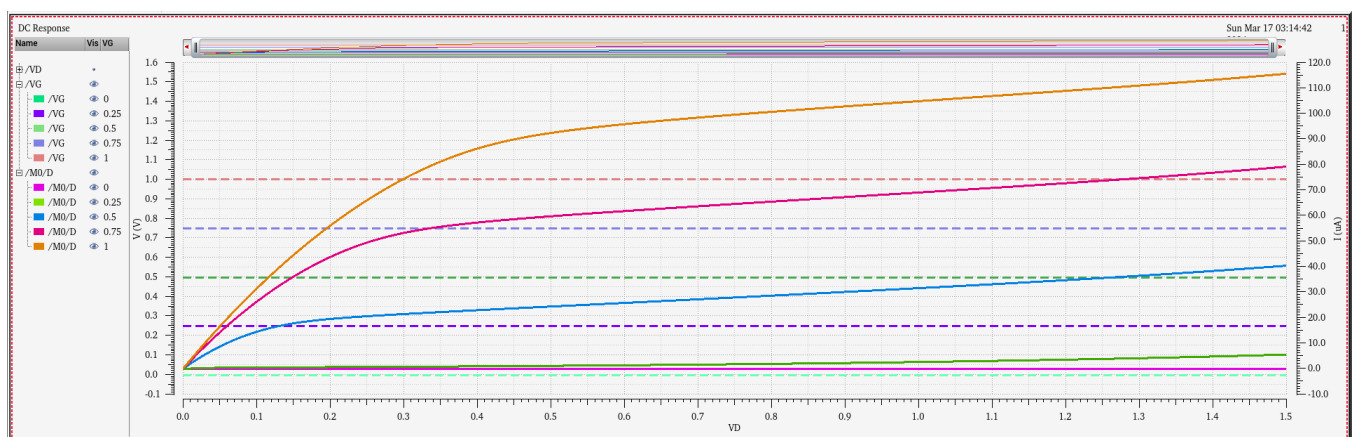


Figure 5 I_D vs V_{DS} @ $V_{gs} = [0, 1] V$ step 0.25V.

Check: Your result must show these results.

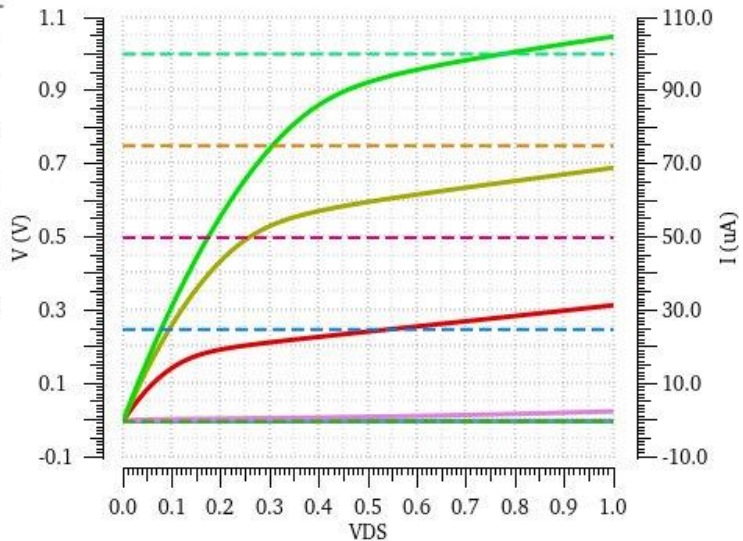
- Simulate curves I_D vs V_{GS} @ $V_{gs} = [0, 1] V$ step 0.25V.

LABORATORY 1 – MOS TRANSISTOR CHARACTERIZATION

DC Response

Mon Nov 25 10:34:33 2024 1

Name		VGS
/VGS		
/VGS		0
/VGS		0.25
/VGS		0.5
/VGS		0.75
/VGS		1
/VDS		
Id		
/NMOS1/D (VGS=0)		0
/NMOS1/D (VGS=0.25)		0.25
/NMOS1/D (VGS=0.5)		0.5
/NMOS1/D (VGS=0.75)		0.75
/NMOS1/D (VGS=1)		1

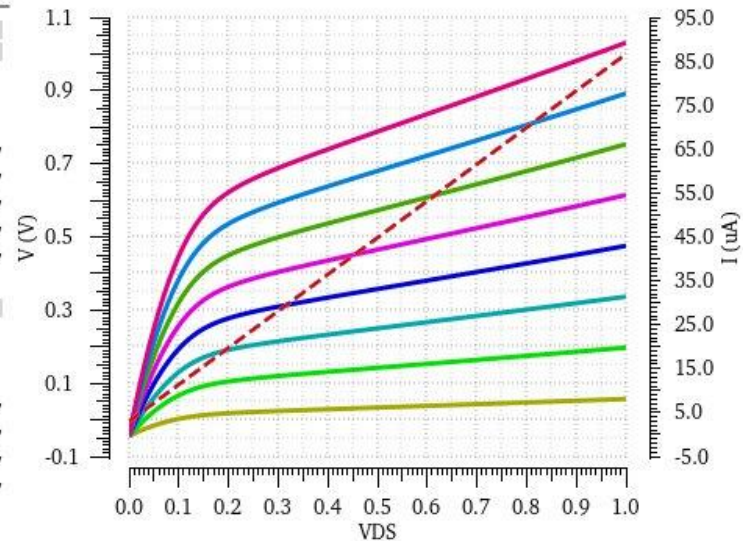


➤ Simulate curves I_D vs V_{DS} @ $W = [30,210]$ nm step 30nm.

DC Response

Mon Nov 25 10:54:36 2024 1

Name		W
/VGS		
/VDS		
/VDS		3e-8
/VDS		6e-8
/VDS		9e-8
/VDS		1.2e-7
/VDS		1.5e-7
/VDS		1.8e-7
/VDS		2.1e-7
/VDS		2.4e-7
Id		
/NMOS1/D (W=3e-08)		3e-8
/NMOS1/D (W=6e-08)		6e-8
/NMOS1/D (W=9e-08)		9e-8
/NMOS1/D (W=1.2e-07)		1.2e-7
/NMOS1/D (W=1.5e-07)		1.5e-7
/NMOS1/D (W=1.8e-07)		1.8e-7
/NMOS1/D (W=2.1e-07)		2.1e-7



➤ Simulate curves I_D vs V_{DS} @ $L = [30,240]$ nm step 30nm.

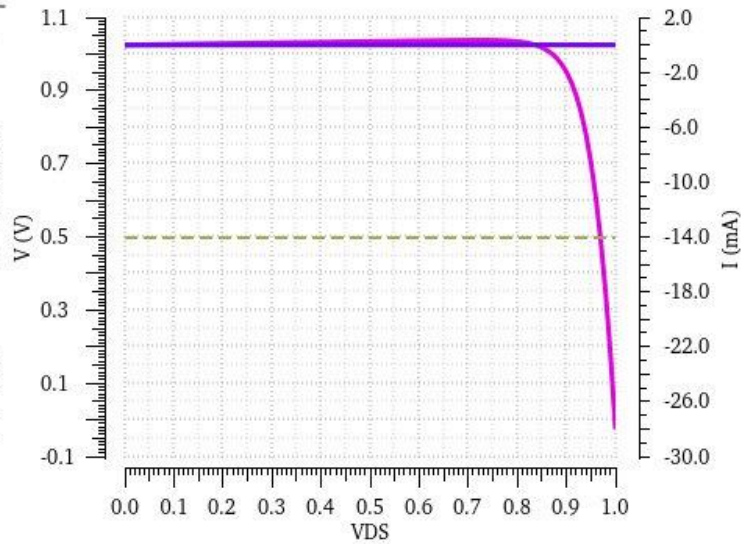


LABORATORY 1 – MOS TRANSISTOR CHARACTERIZATION

DC Response

Mon Nov 25 11:00:01 2024 1

Name	L
/VGS	
/VGS	3e-8
/VGS	6e-8
/VGS	9e-8
/VGS	1.2e-7
/VGS	1.5e-7
/VGS	1.8e-7
/VGS	2.1e-7
/VDS	
/NMOS1/D	
/NMOS1/D	3e-8
/NMOS1/D	6e-8
/NMOS1/D	9e-8
/NMOS1/D	1.2e-7
/NMOS1/D	1.5e-7
/NMOS1/D	1.8e-7
/NMOS1/D	2.1e-7



EXPERIMENT 3

Objective: Create layouts for MOS devices.

Requirements:

- Create layout of a 120n/60n NMOS_VTL and a 50n/40n PMOS_VTL.
- Show DRC confirmation and corresponding schematic with proof of LVS.

Instructions:

➤ In this experiment, students will consider how the transistors are built. Designers need to understand the physical implementation of circuits because it has a major impact on performance, power, and cost. Easiest to understand by viewing both top and cross-section of a wafer in a simplified manufacturing process, where:

One is the top view, obtained by looking down on a wafer.

The other is the cross-section, obtained by slicing the wafer through the middle of a transistor and looking at it edge-wise.

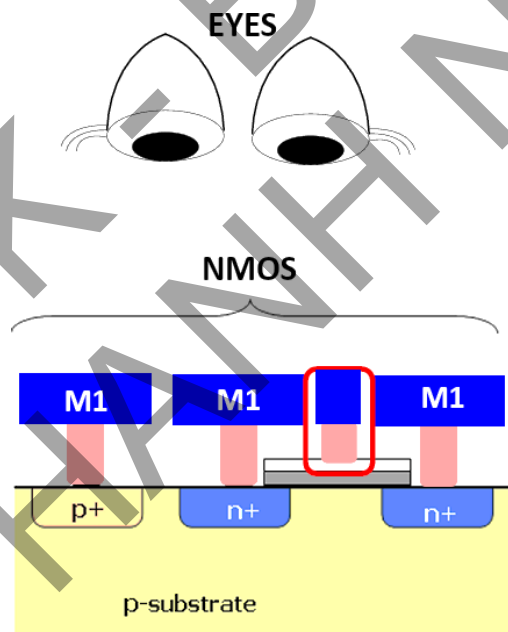


Figure 6 Cross section of an NMOS transistor.

➤ Students begin by looking at the cross-section of a complete NMOS transistor, then look at the top view of the same NMOS transistor and define a set of masks used to manufacture the different parts of the NMOS transistor.

➤ According to layout instructions in lab 0, this lab only mentions layout steps to perform.

1. Add **n-active** (n-islands).

2. Add Poly (**PO**) for the gate.
3. Make drain, source, and bulk connections (contacts).
4. Create **pwell**.
5. Overlap the two active regions with the correct types of **implants**.
6. Create contacts for four terminals (**metal1**).

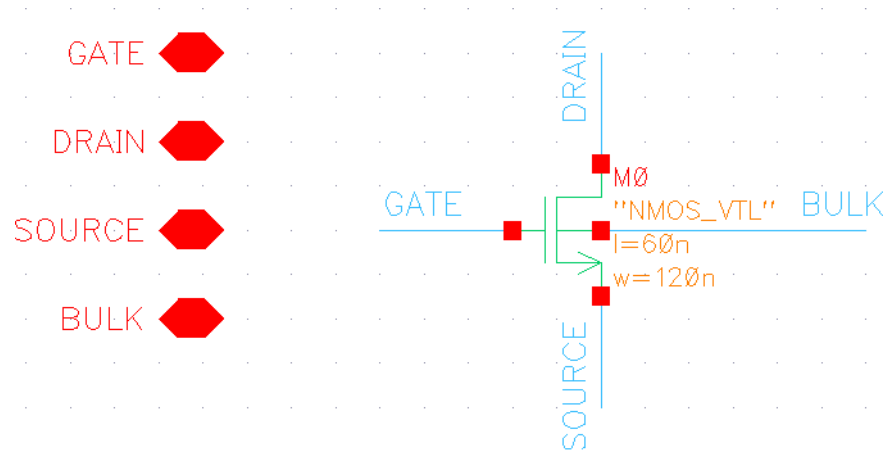
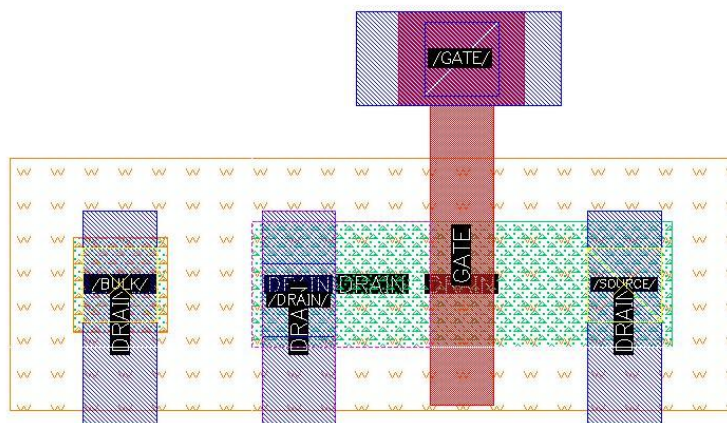


Figure 7 NMOS schematic.

Check:

- Layout of a 120n/60n NMOS_VTL with DRC confirmation and corresponding schematic with proof of LVS.



LABORATORY 1 – MOS TRANSISTOR CHARACTERIZATION

The top screenshot shows the 'NMOS.drc.results' window. The 'Check / Cell' list includes:

Check / Cell	Results
Check Well,1	0
Check Well,2	0
Check Well,4	0
Check Poly,1	0
Check Poly,2	0
Check Poly,3	0
Check Poly,4	0
Check Poly,5	0
Check Poly,6	0
Check Active,1	0
Check Active,2	0
Check Active,3	0
Check Active,4	0
Check Implant,1	0
Check Implant,2	0

The bottom screenshot shows the 'Comparison Results' window for 'NMOS'. The 'CELL COMPARISON RESULTS (TOP LEVEL)' section displays:

```

# # # # #
# # # CORRECT # # #
# # # # #
  
```

Below this, the 'NUMBERS OF OBJECTS' table is shown:

	Layout	Source	Component Type
Ports:	4	4	
Nets:	4	4	

➤ Layout of a 50n/50n PMOS_VTL with DRC confirmation and corresponding schematic with proof of LVS.



LABORATORY 1 – MOS TRANSISTOR CHARACTERIZATION

The image displays two screenshots of the Calibre RVE v2021.2.28.15 interface. The top screenshot shows a layout of a PMOS transistor with labels for DRAIN, BULK, SOURCE, GATE, and GATE. The bottom screenshot shows the verification results for the PMOS cell.

Verification Results:

Check / Cell	Results
Check Well.1	0
Check Well.2	0
Check Well.4	0
Check Poly.1	0
Check Poly.2	0
Check Poly.3	0
Check Poly.4	0
Check Poly.5	0
Check Poly.6	0
Check Active.1	0
Check Active.2	0
Check Active.3	0
Check Active.4	0
Check Implant.1	0
Check Implant.2	0
Check Implant.3	0
Check Implant.4	0

Rule File Pathname: /home/admin/Documents/virtuoso/dcd/inv/layout/DRC/_calibreDRC.rul_

Well and Pwell must not overlap

Comparison Results:

Layout Cell / Type	Source Cell	Nets	Instances	Ports
PMOS	PMOS	4L, 4S	1L, 1S	4L, 4S

Cell PMOS Summary (Clean)

CELL COMPARISON RESULTS (TOP LEVEL)

LAYOUT CELL NAME: PMOS
SOURCE CELL NAME: PMOS

NUMBERS OF OBJECTS

	Layout	Source	Component Type
Ports:	4	4	
Nets:	4	4	

